

Electronic Supplementary Information for

The lower rather than higher density charge carrier determines the NH₃-sensing nature and sensitivity of ambipolar organic semiconductors

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Content List

1. Chemicals and Characterization

2. Electrical measurements and Gas sources for sensing experiments

3. Figs. S1-S2 and Table S1

1. Chemicals and Characterization

Bis(phthalocyaninato) rare earth(III) complexes **1-4** were synthesized according to previously published procedure.¹ All other reagents and solvents were of reagent grade and used as received.

Electrochemical measurements were conducted using a CHI760D voltammetric analyzer based on the procedure reported previously.² The aggregates were fabricated using the QLS method following previously published process,³ which were transferred onto the quartz substrate for UV-vis absorption spectra measurement and onto the bare SiO₂/Si substrate for X-ray diffraction (XRD), ultraviolet photoelectron spectrometry (UPS), and atomic force microscope (AFM) measurements. Electronic absorption spectra were recorded on a Hitachi U-4100 spectrophotometer. XRD experiments were carried out on a Rigaku D/max-B X-ray diffractometer with copper (K α) radiation ($\lambda = 1.5406 \text{ \AA}$). UPS measurements were performed using a HeI α (21.22 eV) discharge lamp in a VG ESCALAB 220i-XL UHV photoelectron spectroscopy system which consists of an analysis chamber interconnected to a preparation chamber. AFM images were collected under ambient conditions using the tapping mode with a NanoscopeIII/Bioscope scanning probe microscope from digital instruments.

2. Electrical measurements and Gas sources for sensing experiments

OFET devices were fabricated from the aggregates **1-4** in the typical top-contact/bottom-gate geometry on the hexamethyldisilazane (HMDS)-treated doped-Si/SiO₂ (300 nm thickness, capacitance $C_0=10 \text{ nF cm}^{-2}$) substrates, in which the source and drain gold electrodes are vacuum-deposited on the top of the aggregates employing a shadow mask.⁴ The drain-source current (I_{ds}) versus drain-source voltage (V_{ds}) characteristic was obtained with a Hewlett-Packard (HP) 4140B parameter analyzer at room temperature. Experimental data were analyzed

using standard field-effect transistor equations reported previously.⁵ The direct current–voltage (I–V) measurements for the aggregates of **1-4** deposited on insulating SiO₂ substrates with the ITO interdigitated electrodes were performed using a Keithley 6517 electrometer with an incorporated DC voltage supply. The NH₃-sensing properties of samples **1-4** have been examined by exposing the corresponding aggregates to different concentrations of ammonia and measuring the current changes of the aggregates at a constantly polarized voltage of 5 V.

The desired ammonia concentration was produced by diluting a mixture NH₃/Ar (1000 ppm NH₃, from Air Liquid, France) with dry Ar using two mass flow controllers (total mass flow: 0.5 L min⁻¹).

Reference

- 1 G. Lu, M. Bai, R. Li, X. Zhang, C. Ma, P.-C. Lo, D. K. P. Ng and J. Jiang, *Eur. J. Inorg. Chem.*, 2006, **18**, 3703.
- 2 D. Gao, X. Zhang, X. Kong, Y. Chen and J. Jiang, *ACS Appl. Mater. Interfaces*, 2015, **7**, 2486.
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- 4 Y. Chen, W. Su, J. Jiang, X. Li and Y. Liu, *J. Am. Chem. Soc.*, 2005, **127**, 15700.
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3. Figs. S1-S2 and Table S1

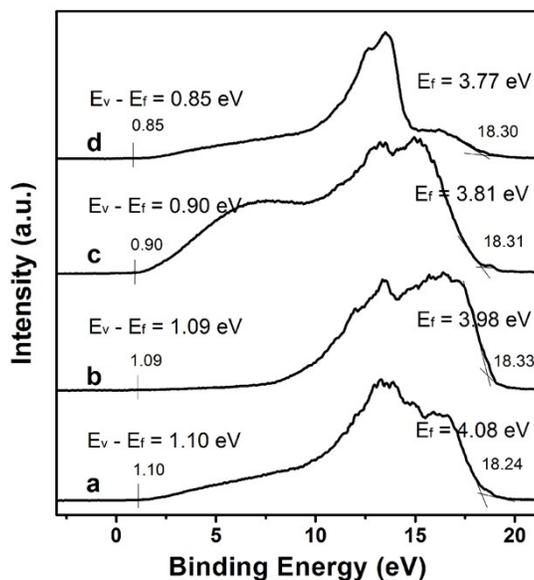


Fig. S1 UPS spectra (UV excitation by HeI α =21.22 eV) of the aggregates **1-4** (a-d). The Fermi level was obtained using the formula $E_f = h\nu - (E_{\text{cut-off}}^{\text{max}} - E_{\text{cut-off}}^{\text{min}})$. The minimum kinetic energy $E_{\text{cut-off}}^{\text{min}}$ at the left-hand part ($E_{\text{cut-off}}^{\text{min}} = E_v - E_f = E_{\text{HOMO}} - E_f$), corresponds to electrons from the HOMO level.

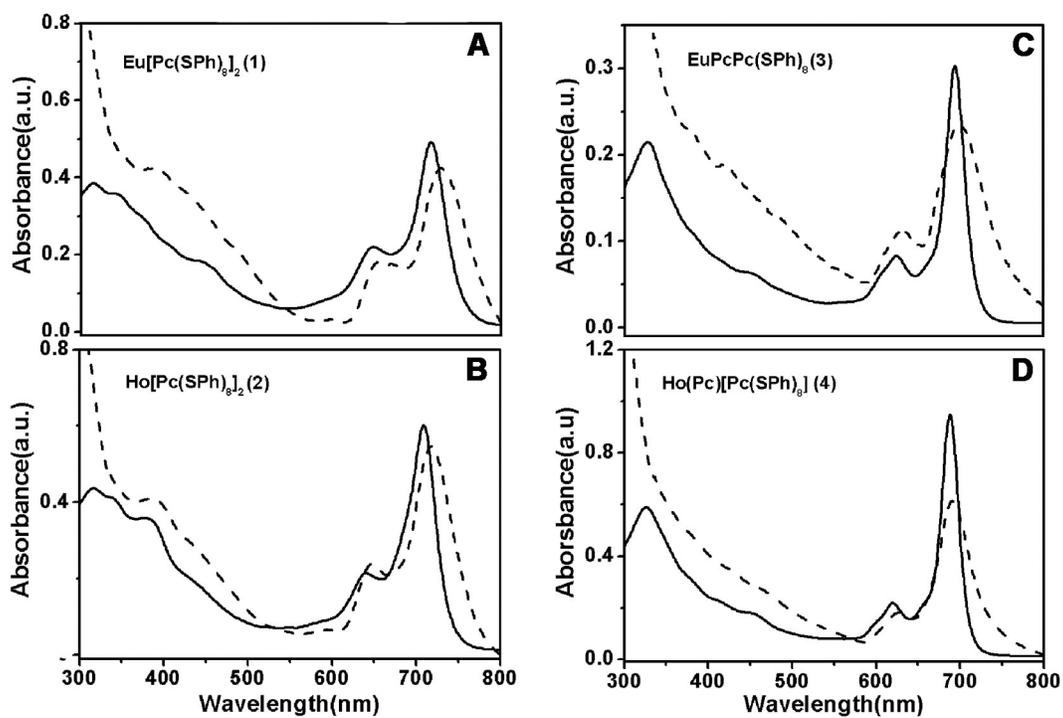


Fig. S2 UV-vis absorption spectra of **1-4** in CH_2Cl_2 solution (solid line) and self-assembled aggregates (dash line).

Table S1. Half-wave redox potentials of **1-4** (V vs. SCE) in CH₂Cl₂ containing 0.1 M TBAP (Tetrabutylammonium perruthenate) and maximum Q band absorption of compounds **1-4** in CH₂Cl₂ solution and self-assembled nanostructures.

Compound	E_{Oxd1}	E_{Red1}	E_{Red2}	E_{Red3}	$\Delta E^{\circ}_{1/2^a)}$	$\Delta E^{\circ\prime}_{1/2^a)}$	LUMO/eV ^{b)}	HOMO/eV ^{b)}	$\Delta\lambda_{\text{max}}/\text{nm}$		$\Delta\lambda_{\text{max}}/\text{nm}^c)$
									solution	aggregate	
1	+0.67	+0.30	-0.84	-1.08	0.37	1.14	-3.60	-4.74	716	730	14
2^{d)}	+0.66	+0.28	-0.85	-1.04	0.38	1.13	-3.59	-4.72	709	719	10
3	+0.64	+0.22	-0.90	-1.25	0.42	1.12	-3.54	-4.66	694	702	8
4^{d)}	+ 0.58	+0.17	-0.92	-1.21	0.41	1.09	-3.52	-4.61	688	691	3

^{a)} $\Delta E^{\circ}_{1/2} = E_{\text{Oxd1}} - E_{\text{Red1}}$, $\Delta E^{\circ\prime}_{1/2} = E_{\text{Red1}} - E_{\text{Red2}}$;

^{b)} HOMO (eV) = - 4.44eV - e E_{Red1} , LUMO (eV) = - 4.44eV - e E_{Red2} ;

^{c)} $\Delta\lambda_{\text{max}} = \lambda_{\text{max}}(\text{aggregate}) - \lambda_{\text{max}}(\text{solution})$;

^{d)} Cited from G. Lu, M. Bai, R. Li, X. Zhang, C. Ma, P.-C. Lo, D. K. P. Ng and J. Jiang, *Eur. J. Inorg. Chem.*, 2006, **18**, 3703.